

PATENT

Reply Under 37 CFR 1.116
Expedited Procedure
Technology Center 1700

IN THE UNITED STATES PATENT
AND TRADEMARK OFFICE

Applicants:	Young Sun Hwang et al.)	I hereby certify that this paper (along with
)	any paper referred to as being attached or
Serial No.:	10/719,083)	enclosed) is being transmitted via EFS-
)	Web to the U.S. Patent and Trademark
Conf. No.:	2261)	Office on July 19, 2007 .
)	
Filed:	November 21, 2003)	
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Title:	METHODS FOR FORMING)	
	FINE PHOTORESIST)	
	PATTERNS)	
)	
Group Art Unit:	1765)	
)	/ Sandip H. Patel /
Examiner:	Patricia Ann George)	Sandip H. Patel (Reg. No. 43,848)
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Attorney Docket No.:	30205/39513)	

RESPONSE TO FINAL OFFICIAL ACTION

Mail Stop AF
Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Dear Sir:

This paper is being submitted in response to the final official action dated April 19, 2007.

Remarks begin on page 2 of this paper.

A complete listing of the existing claims is not required (or presented herein) because no changes are being made to the claims, no claims are being canceled, and no claims are being added. See 37 CFR § 1.121(c).